
ECFA R&D electronics

DRDT 7.7 Technologies & Tools

15/3/2023 CERN

Conveners:

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¹RAL, STFC, UK

²CERN



Agenda

- Introducing the challenges of collaborative work at HEP 10'
 - *Kostas Kloukinas, CERN*

- Access to advanced silicon technologies for the HEP community via EUROPRACTICE 20'
 - *Paul Malisse, EUROPRACTICE IC service, IMEC IC-link, BE.*

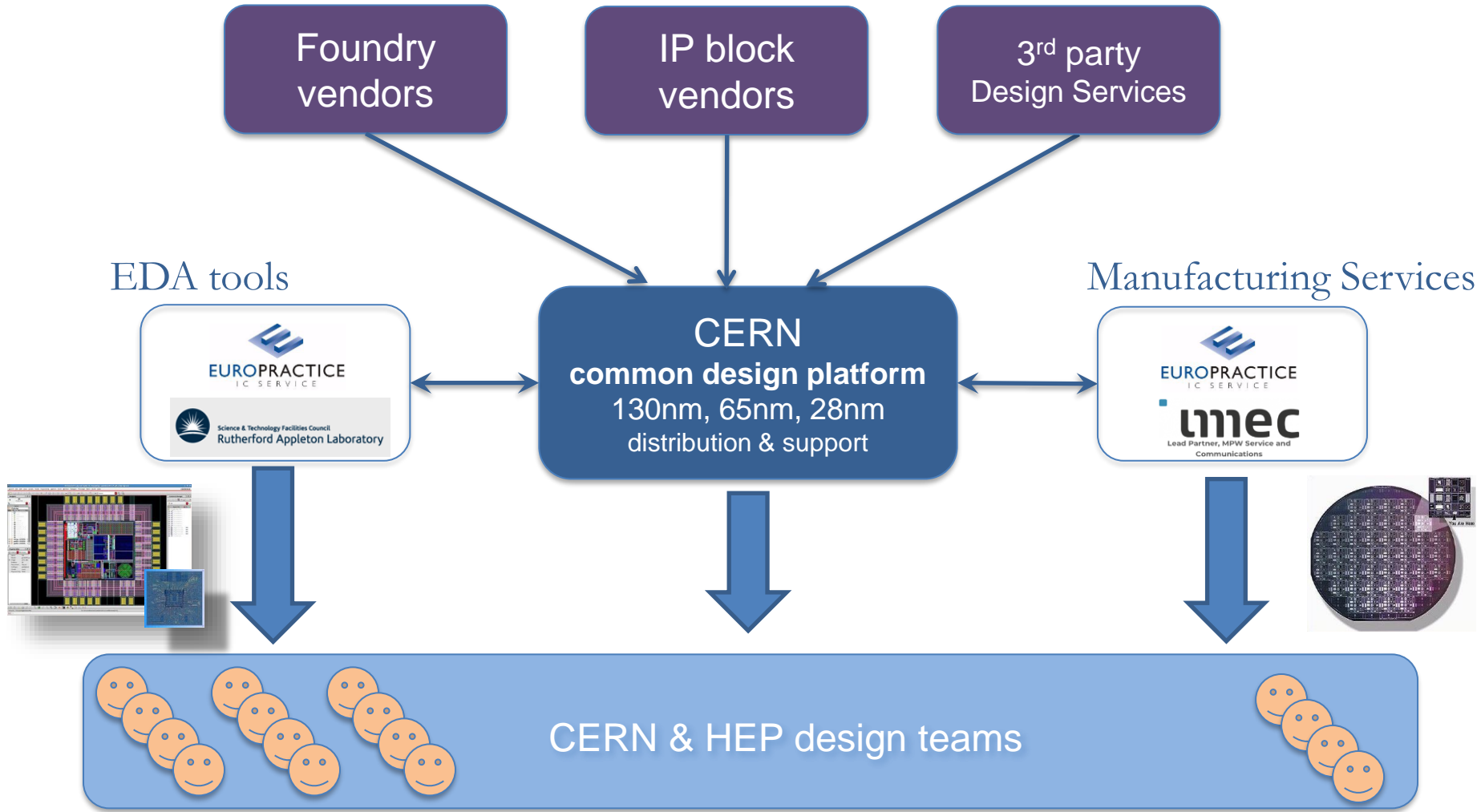
- Access to modern EDA tools and IP block sharing in HEP community via EUROPRACTICE 20'
 - *Mark Willoughby, EUROPRACTICE design tools service, RAL, STFC, UK*

- Challenges in designing ASICs for HEP Experiments 20'
 - *Adithya Pulli, CERN*

- *Open Discussion* 20'



ASIC Design Support for HEP



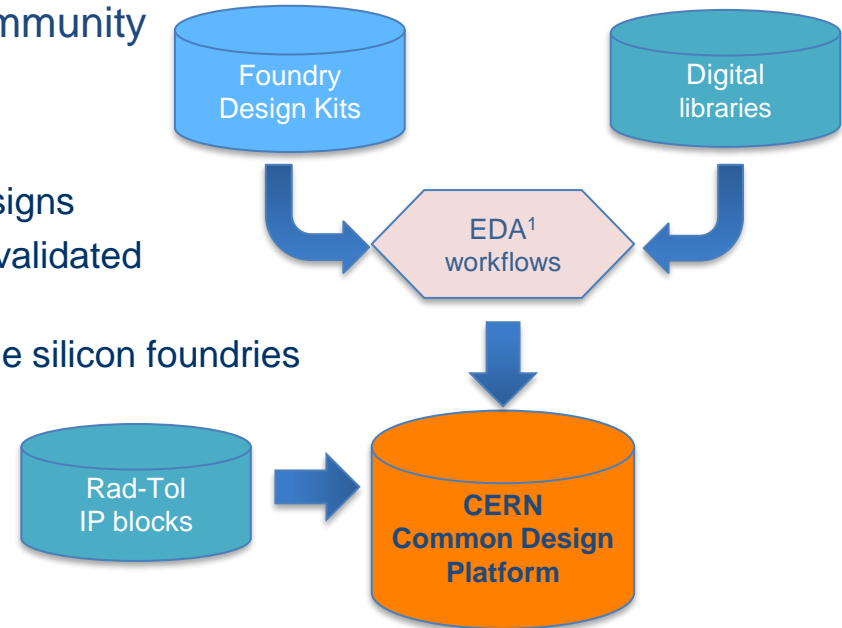
asic.support@cern.ch

ASIC Design Platforms for HEP

- “Common ASIC design platforms” for HEP community

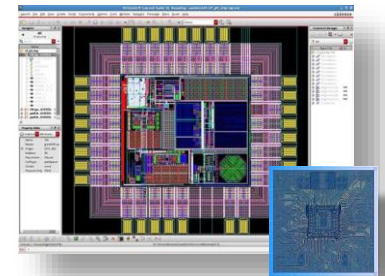
- Develop and Provide:

- **Design kits** that support analog and digital designs
- **Design Workflows** that are standardized and validated using selected EDA tools
- **Compatible Design Workflows** across multiple silicon foundries
- **Rad-Tol IP blocks**
- Maintenance
- Technical Support
- Training



- Timeline

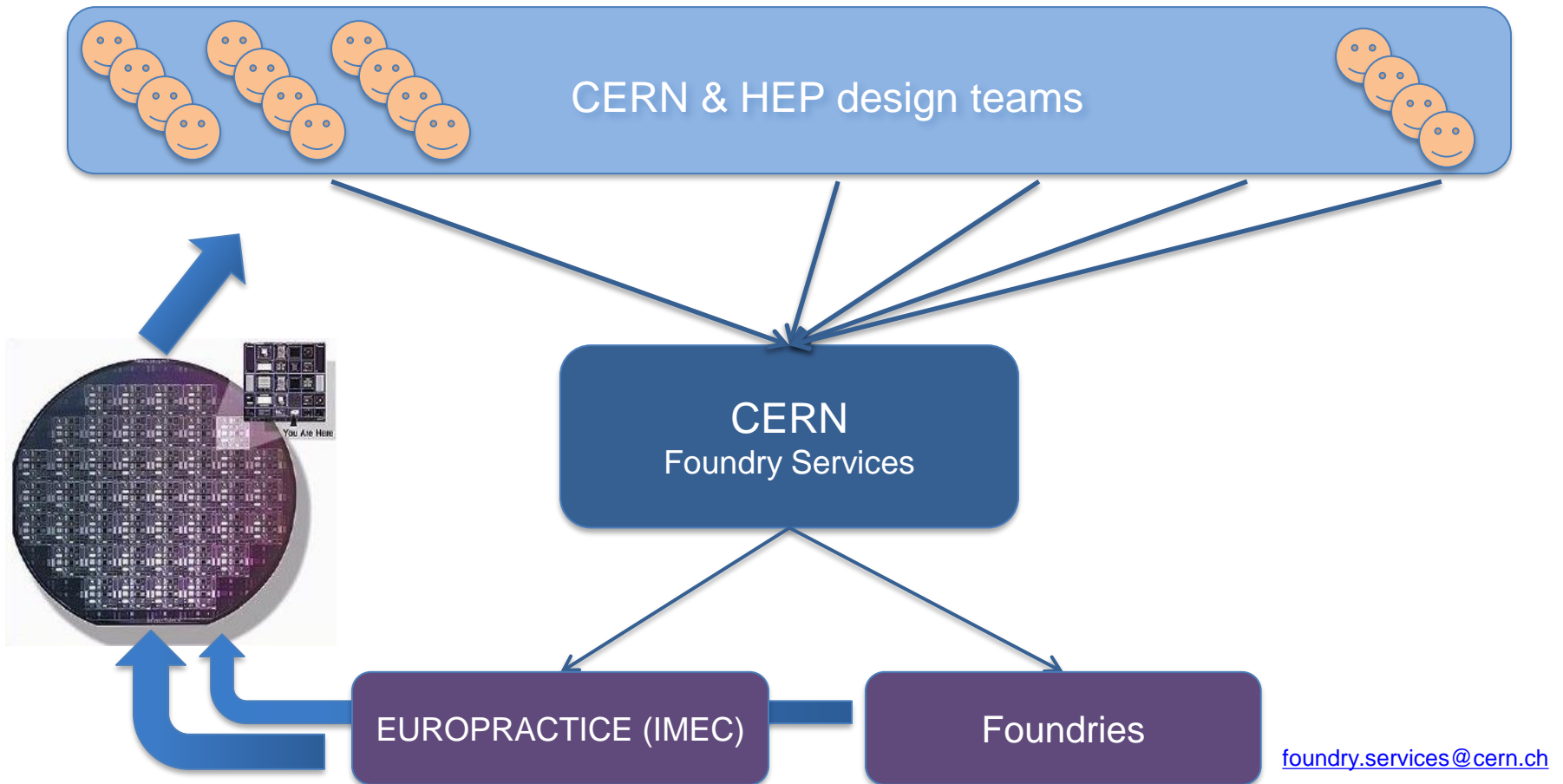
- 1997 IBM 250nm
- 2009 IBM 130nm
- 2014 TSMC 65nm & 130nm
- 2020 TSMC 28nm





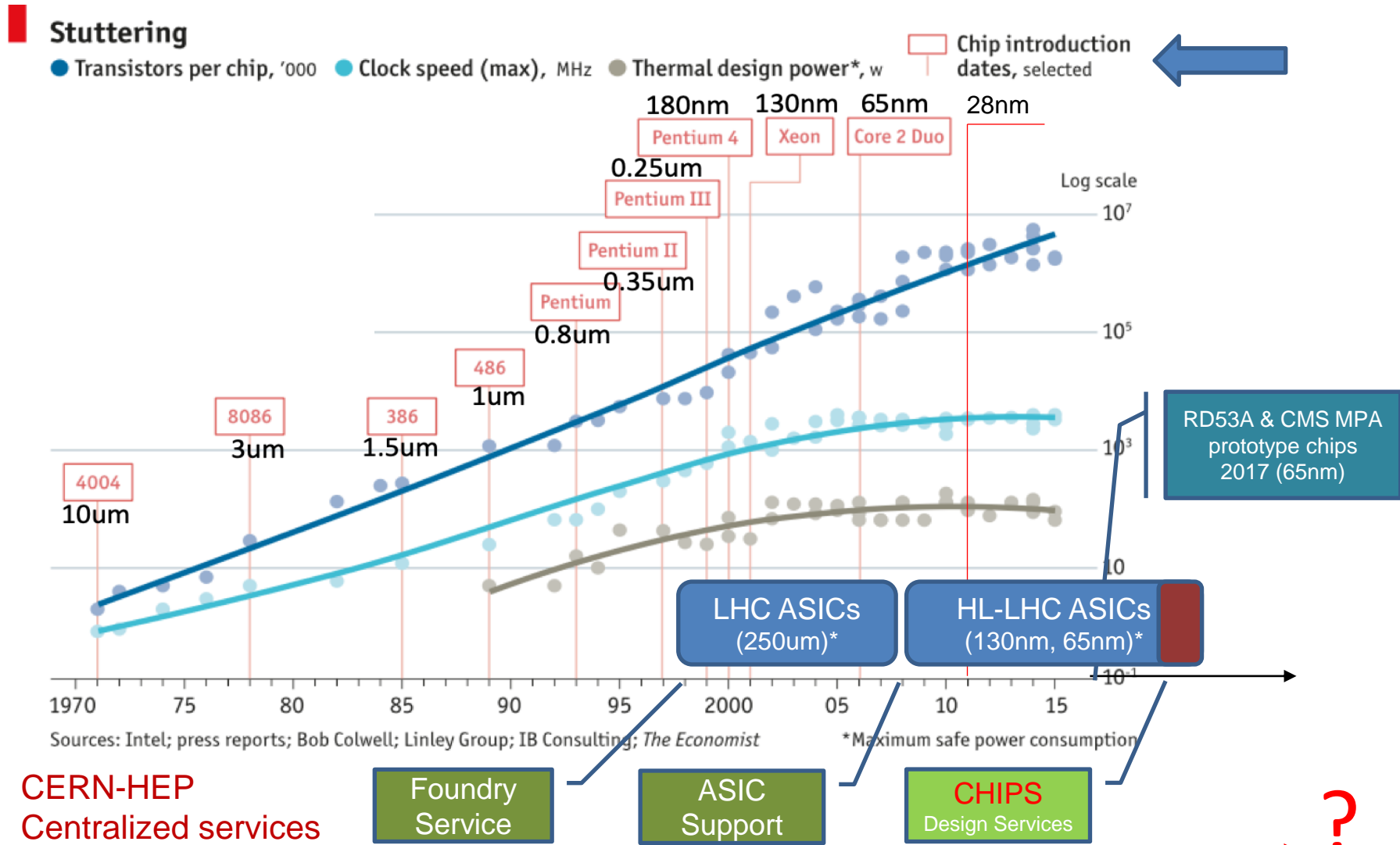
Foundry Access Services

- Organize prototyping Multi Project Wafer runs, for sharing fabrication costs
- Coordinate Engineering & Production runs





Technology evolution and HEP



Challenges in ASIC design @ HEP

- Technology Challenges

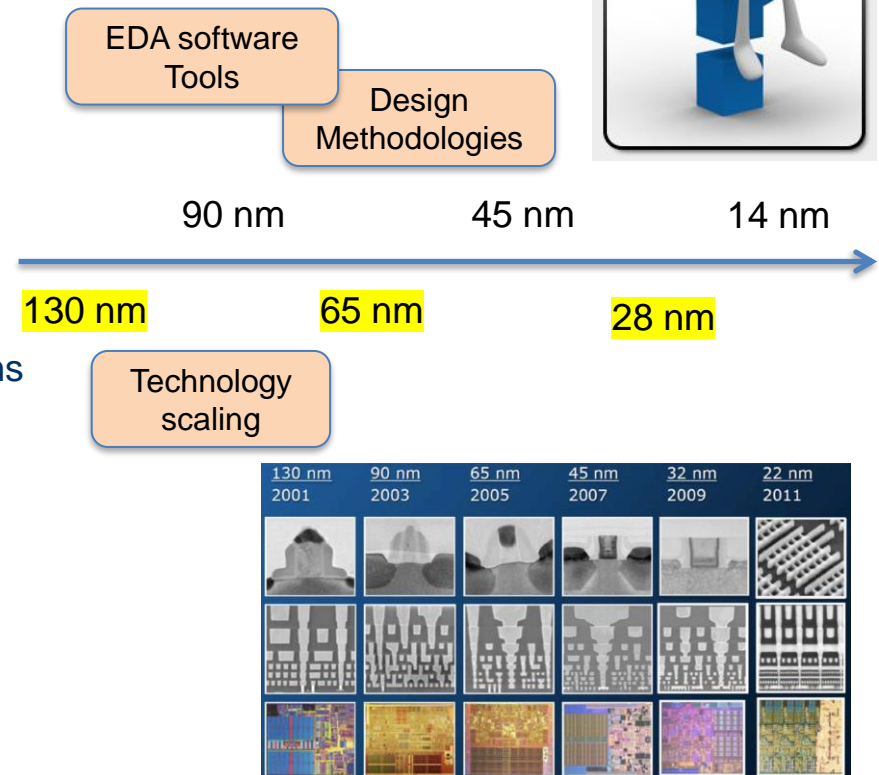
- Complex deep-submicron silicon manufacturing processes
- Powerful, Flexible but highly Complex EDA Tools

- Design Challenges

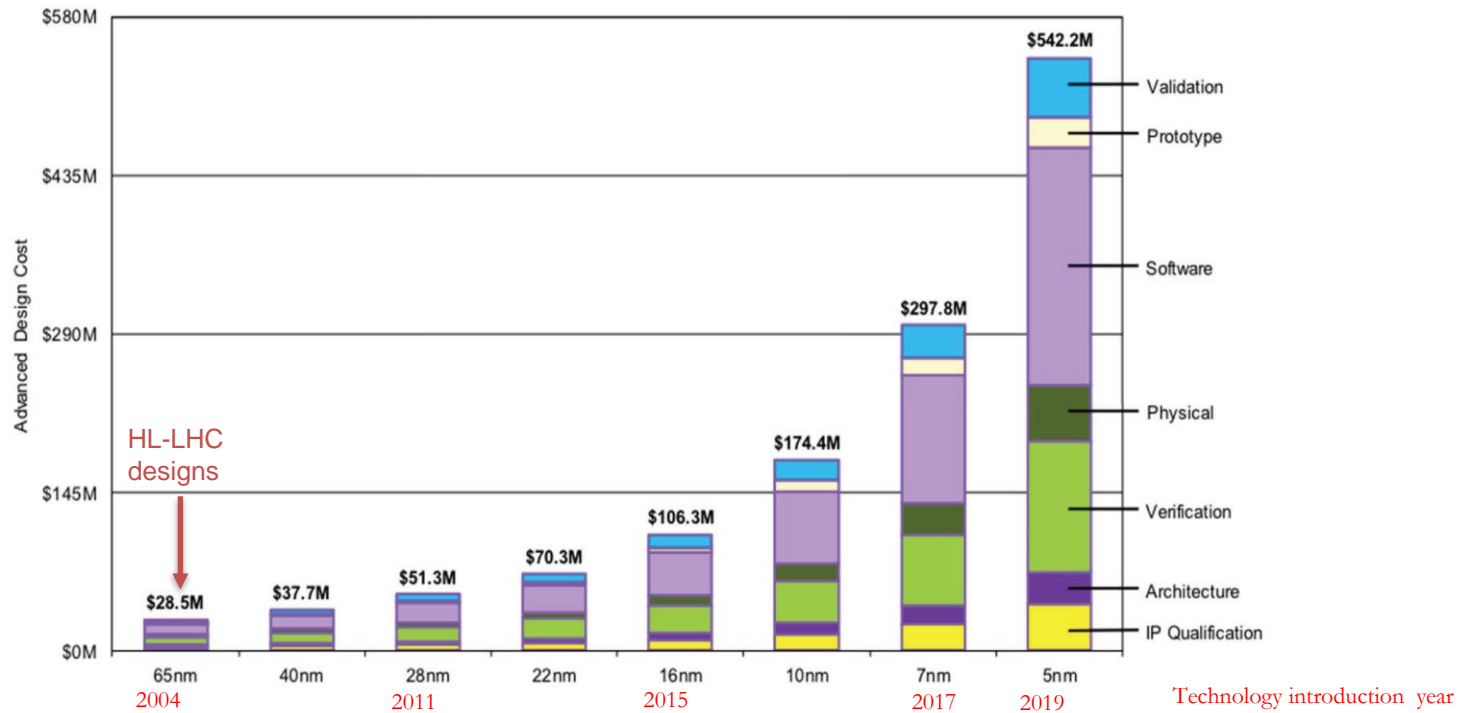
- Designs of increasing complexity and size
- Novel designs for scientific instrumentation
- Radiation Tolerance

- Productivity Requirements

- Large, fragmented, multinational design teams
- Designers with different levels of expertise
- Work on common design projects
- Costly technologies
- Importance of 'first-time-right' designs !



ASIC development costs



Chip Design and Manufacturing Cost under Different Process Nodes: Data Source from IBS*

- Steep investment for node sizes <16nm. But combine strong performance with lower power consumption
- Design verification skills and effort are increasingly more important
- Cost per transistor continues to fall even at 5nm, but this is relegated to those who have large wafer volume



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A nighttime photograph of the ATLAS detector dome at CERN, illuminated from within, set against a dark blue sky with stars and a meteor streak.

Thank You



Addressing the Challenges

■ Technology Challenges

- Augment EDA Tools -> EURO PRACTICE
- Access to Advanced technologies -> EURO PRACTICE
- Integrate support for "More than Moore" technologies
 - 3D Interconnect & Advanced Packaging
 - SiPh
 - CMOS Imaging (monolithic sensors)
 - Specialty embedded devices

■ Design Challenges

- System Architect role
- System Level Modeling and Simulations
- Design Verification at System Level and component level
- Establish & Conform to a Rad-Tol SoC infrastructure

■ Productivity Requirements

- Establish a Collaborative Work structure



Enablers for Collaborative Work

■ Technical Framework

- Comprehensive “common design platforms”
 - Foundry PDKs & Foundry IP blocks
 - Rad-Tol IP blocks and IP block repository
 - Rad-Tol SoC infrastructure
 - Design & Verification methodologies
- Access to common EDA tools
- Maintenance, Training & Support services

■ Legal Framework

- 3-way NDAs with Foundries permitting technology data exchange
- Commercial Contracts with Foundries
- EULAs of EDA tool providers permitting IP block sharing
- IP block sharing agreements among design teams
- Export Control regulations

